

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Masuda et al.
Appl. No.	:	10/564,510
Filed	:	January 12, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Chu, John S Y
Group Art Unit	:	1752

OK TO ENTER: /JSC/

03/15/2008

**RESPONSE TO OFFICE ACTION****Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **December 12, 2007**, please amend the above-referenced application as follows:

A **listing of claims** begins on page 2 of this paper for the Examiner's convenience. No amendments have been made

**Remarks/Arguments** begin on page 5 of this paper.